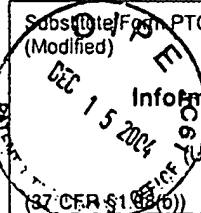



Substitute Form PTO-1449 (Modified)  Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.96(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-927001	Application No. 10/824,305
	Applicant Richard Schenker		
	Filing Date April 13, 2004	Group Art Unit 2873	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AI							
	AJ							
	AK							
	AL							
	AM							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
C.C.	AN	Konstantinos Adam et al., "Polarization Effects in Immersion Lithography", Optical Microlithography XVII, Proceedings of SPIE Vol. 5377, pgs. 329-343, 2004
C.C.	AO	Richard Schenker et al., "Material Limitations to 193-nm Lithographic System Lifetimes", SPIE Vol. 2726, pgs. 698-706
C.C.	AP	Richard E. Schenker et al., "Ultraviolet-induced densification in fused silica", J. Appl. Phys. 82 (3), August 1, 1997, pgs. 1065-1071
C.C.	AQ	G. de Zwart et al., "Performance of a Step and Scan System for DUV Lithography", SPIE Vol. 3051, pgs. 817-830
C.C.	AR	U.S. Patent Application Serial No. 10/813,453, filed March 29, 2004, "LITHOGRAPHY USING CONTROLLED POLARIZATION"

Examiner Signature 	Date Considered 6/3/05
EXAMINER: Initials/citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	